

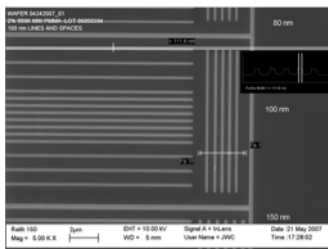
PMMA/Copolymer Positive Resists

E-beam Processing

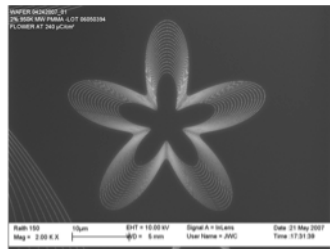
FEATURES

- Positive tone
- E-beam and X-ray imageable
- Wide range of film thicknesses
- Excellent adhesion to most substrates

950K PMMA



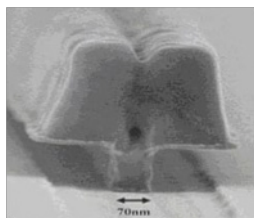
100 nm thick
100 nm L/S fully cleared



100 nm thick flower pattern
100 nm target width

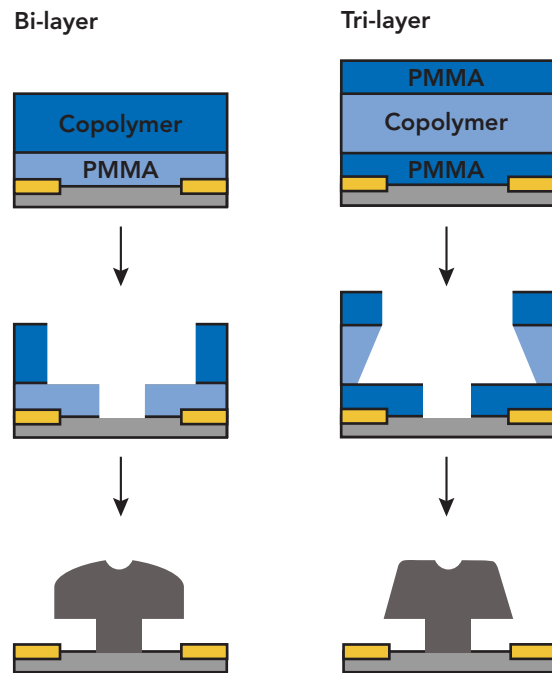
APPLICATIONS

- Direct-write e-beam lithography
- T-gates
- Temporary bonding adhesive
- Protective coating
- Metal lift-off



Metal T-gate

SCHEMATIC OF T-GATE PROCESSES



PRODUCT LINE

- 950K PMMA in chlorobenzene or anisole
- 495K PMMA in chlorobenzene or anisole
- Copolymer in ethyl lactate
- MIBK:IPA Developer blends for resolution/throughput control